

Product Identification

Film Name: PECVD Zero Stress Nitride
 Process ID: D01FSN
 Scientific: Silicon Nitride - SiN
 Classification: Custom

Applications

Passivation Thick Structures
 Insulation Layer
 Inter-layer Dielectric Encapsulation
 Masking Adhesion Layer
 Wear Coating
 Patterning

Features

Low Cost
 Variable Processing Parameters
 Large Batch Capacity
 Adjustable Stress Range

Standards & Guarantees

Inspection: Standard I/O - First & Last
 Guaranteed: Thickness (On Si Monitors)
 Guaranteed: Refractive Index (On Si Monitors)
 Reference: Stress (On Si Monitors) (Not Guaranteed)

Items may vary when ordering outside the standard

Film Specifications

Film Thickness	Standard	1000A to 10,000A ± 10%
	Adjustable Range	500A to 100,000A ± 10%
Refractive Index	Standard	2.00 ± .05
	Adjustable Range	Fixed
Film Uniformity	Edge to Edge	10%
	Across Load	10%
Deposition Temp	Standard	380C
	Adjustable Range	100C to 600C
Film Stress	Standard	0 MPa ± 100MPa
	Adjustable Range	None

Film Properties

Electrical	Insulating Quality	N/A
	Dielectric Constant	N/A
Mechanical	Hydrogen Inclusion	N/A
	Scratch Protect	N/A
	Masking Ability	N/A
	Diffusion Barrier	N/A
	Thermal Stability	N/A
Etch Rate	N/A	N/A
Hydrology	N/A	N/A